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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/623,678	07/21/2003	David L. Carnahan	NANO-6	5076	
75	90 08/24/2004		EXAMINER		
Pandiscio & Pandiscio			BERRY, RENEE R		
470 Totten Pone Waltham, MA			ART UNIT	PAPER NUMBER	
***************************************			2818		
			DATE MAILED: 08/24/200	4	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Applica	ation No.	Applicant(s)				
		10/623,	10/623,678 CARNAHAN, DAVID L.		/ID L.			
Office Action Summary		Examin	Examiner Art Unit		1			
		Renee F	R Berry	2818	کسھ			
Period fo	The MAILING DATE of this commu or Reply	nication appears on t	he cover sheet w	vith the correspondence ad	dress			
THE   - External after   - If the   - If NO   - Failure   Any I	ORTENED STATUTORY PERIOD MAILING DATE OF THIS COMMUN nsions of time may be available under the provision SIX (6) MONTHS from the mailing date of this comperiod for reply specified above is less than thirty period for reply is specified above, the maximum or to reply within the set or extended period for repreply received by the Office later than three months and patent term adjustment. See 37 CFR 1.704(b).	NICATION.  ns of 37 CFR 1.136(a). In no numication.  (30) days, a reply within the statutory period will apply and ly will, by statute, cause the a	event, however, may a statutory minimum of thi I will expire SIX (6) MO application to become A	reply be timely filed  rty (30) days will be considered time!  NTHS from the mailing date of this country  BANDONED (35 U.S.C. § 133).	y. ommunication.			
Status			·					
1)	Responsive to communication(s) fi	led on						
2a)□	This action is <b>FINAL</b> .	2b)⊠ This action is	s non-final.					
3)□	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Disposit	ion of Claims							
5)□ 6)⊠ 7)□	Claim(s) <u>1-53</u> is/are pending in the 4a) Of the above claim(s) <u>1-10</u> is/are Claim(s) is/are allowed. Claim(s) <u>11-53</u> is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restrict the claim(s)	re withdrawn from co		-				
Applicat	ion Papers							
9)□	The specification is objected to by t	he Examiner.						
10)⊠	) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.							
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
11)□	Replacement drawing sheet(s) including The oath or declaration is objected							
Priority (	under 35 U.S.C. § 119							
12)□ a)	Acknowledgment is made of a clair  All b) Some * c) None of:  Certified copies of the priorit  Copies of the certified copies application from the Internat	by documents have bury documents have bury sof the priority documents have bury the priority documents bureau (PCT F	een received. een received in ments have bee Rule 17.2(a)).	Application No n received in this National	Stage			
Attachmer			<b>4</b> 0 □ 1=4 ==4	. C				
2) Notice 3) Infor	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review mation Disclosure Statement(s) (PTO-1449 er No(s)/Mail Date		Paper No	Summary (PTO-413) o(s)/Mail Date Informal Patent Application (PT	O-152)			

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### **DETAILED ACTION**

#### Election/Restrictions

Applicant's election without traverse of Group II in the reply filed on April 15, 2004 is acknowledged.

Claims 1-10 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim. Election was made **without** traverse in the reply filed on April 14, 2004.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 11-53 are rejected under 35 U.S.C. 103(a) as being unpatentable over US Patent No. 6,518,194 to Winningham et al. in view of US Patent No. 6,706,402 to Rueckes et al.

In regards to claim 11, Winningham teaches a method for generating a mask having nanoscale pattern, the method comprising: suspending a periodic arrangement of objects on a top surface of supporting liquid at a first given height above a top surface of substrate; and adjusting at least one from a group consisting the top surface of the supporting liquid and the top surface the substrate to position the top surface of the supporting liquid below the top surface

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of substrate so as to deposit the periodic arrangement of objects onto the top surface of the substrate from the suspension on the top surface the supporting liquid; wherein the periodic arrangement of objects maintained over a given area at column 18, lines 56-67 to column 19, lines 1-3.

In regards to claim 12, Winningham teaches a method according to claim 11 wherein the given area at least one square centimeter at column 5, lines 18-22.

In regards to claim 13, Winningham teaches a method according to claim 11 wherein the objects comprise micro-scale particles at column 5, lines 3-11.

In regards to claim 14, Winningham teaches a method according to claim 11 wherein the objects comprise nano-scale particles at column 5, lines 3-11.

In regards to claim 15, Winningham teaches a method according to claim 14 wherein the nano-scale particles have a diameter within the range of about 10 nanometers to about 5000 nanometers at column 5, lines 18-22.

In regards to claim 16, Winningham teaches a method according to claim 11 wherein the objects comprise monodisperse objects with a standard deviation of less than 5% of the particle size at column 14, lines 19-23.

In regards to claim 17, Winningham teaches a method according claim 11 wherein the objects have a generally spherical shape at Figure #1, reference number 18.

In regards to claim 18, Winningham teaches a method according to claim 11 wherein the objects have a generally cubic shape at column 14, lines 61-65.

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In regards to claim 19, Winningham teaches a method according to claim wherein the objects have a generally regular shape at column 14, lines 61-65.

In regards to claim 20, Winningham teaches a method according to claim wherein the objects comprise multiple sizes of particles at column 3, lines 65-67 to column 4, lines 1-2.

In regards to claim 21, Winningham teaches a method according to claim wherein the objects comprises at least one from a group consisting polystyrene, melamine, polydivinylbenzene, polymethyl methacrylate, polytstyrene-co-divinylbenzene), polytstyrene-co-methacrylic methylester) copolymers, and silica at column 7, lines 17-25.

In regards to claim 22, Winningham teaches a method objects comprise according to claim 11 wherein the organic spherical particles at column 14, lines 46-54.

In regards to claim 23, Winningham teaches a method according to claim 11 wherein the organic spherical particles comprise viruses at column 14, lines 46-54.

In regards to claim 24, Winningham teaches a method according claim 11 wherein the substrate comprises an insulator material at column 10, lines 9-19.

In regards to claim 25, Winningham teaches a method according claim 11 substrate comprises a conductor material at column 10, lines 9-19.

In regards to claim 26, Winningham teaches a method according substrate comprises wherein a semiconductor material at column 6, lines 59-62.

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In regards to claim 27, Winningham teaches a method according claim 11 wherein the substrate comprises at least one from a group consisting of glass, silicon, graphite and metal at column 6, lines 50-57.

In regards to claim 28, Winningham teaches a method according claim 11 wherein the substrate comprises a smooth surface having a roughness of less than about 50 nanometers at column 5, lines 18-22.

In regards to claim 29, Winningham teaches a method according claim 11 wherein the substrate comprises a smooth surface having a roughness of less than about 10 nanometers at column 5, lines 18-22.

In regards to claim 31, Winningham teaches a method according to claim further comprising the step of adding a surfactant to the suspension so as to alter a charge of the objects at column 9, lines 51-54.

In regards to claim 32, Winningham teaches a method according to claim 31 wherein the surfactant comprises a cationic surfactant at column 9, lines 51-54.

In regards to claim 33, Winningham teaches a method according to claim 32 wherein the cationic surfactant comprises sodium dodecyl sulfate (C<sub>12</sub>H<sub>25</sub>NaO<sub>4</sub>S) at column 9, lines 51-54.

In regards to claim 34, Winningham teaches a method according to claim 31 wherein the surfactant comprises an anionic surfactant at column 9, lines 51-54.

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In regards to claim 35, Winningham teaches a method according anionic surfactant comprises claim 34 wherein the fatty acid amine at column 15, lines 47-51.

In regards to claim 36, Winningham teaches a method according to claim wherein the surfactant comprises nonionic surfactants at column 9, lines 51-54.

In regard to claim 37, Winningham teaches a method according to claim 36 wherein the nonionic surfactants comprises polyethylene glycol at column 9, lines 51-54.

In regards to claim 41, Winningham teaches a method according to claim 40 wherein the controlled orientation is determined by optical diffraction at column 13, lines 4-5 and column 14, lines 29-31.

In regards to claim 43, Winningham teaches a method wherein the step of depositing the material through the interstices contained in the periodic arrangement objects the mask comprises one from a group consisting of sputtering, evaporation and spraying of a colloidal solution at column 7, lines 34-40.

In regards to claim 44, Winningham teaches a method according to claim 42 wherein the material comprises one from a group consisting of a metal, an insulator, and a semiconductor at column 10, lines 9-25

In regards to claim 50, Winningham teaches a method according to claim 42 wherein the hexagonal monolayer pattern on the substrate comprise a structure at column 14, lines 38-44.

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In regards to claim 51, Winningham teaches a method according claim 42 wherein the pattern on the substrate structure comprises a cubic monolayer at column 14, lines 38-44.

However, Winningham does not teach all the claim limitations.

In regards to claim 38, Rueckes teaches a method according to claim further comprising the step of arranging the objects into monolayer array with a long range order at column 5, lines 51-58.

In regards to claim 39, Rueckes teaches a method according to claim further comprising the step of arranging the objects into a multilayer array with a long range order at column 5, lines 51-58.

In regards to claim 40, Rueckes teaches a method according claim 11 further comprising sequential repetition the step of suspending the periodic arrangement of objects on the top surface of the supporting liquid at the first given height above the top surface the substrate and the step of adjusting at least one of the top surface of the supporting liquid and the top surface of the substrate to position the top surface of the supporting liquid below the top surface of the substrate so as to fabricate multilayer arrays having a controlled orientation of discrete layers.

In regards to claim 42, Rueckes teaches a method for creating a deposition having nanoscale pattern on a substrate, the method comprising: periodic arrangement of objects on a top surface of a supporting liquid at a first given height above suspending a top surface of a substrate; adjusting at least one from a group consisting of top surface of the fluid and the top surface of the

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substrate position the top surface of the supporting liquid below the top surface of the substrate so as deposit the periodic arrangement objects onto the top surface of the substrate from the suspension on the top surface of the fluid, whereby to create mask; and depositing a material through interstices contained in the mask so as create a pattern on the substrate at column 12, lines 31-46.

In regards to claim 45, Rueckes teaches a method according to claim wherein the material comprises a catalytic metal for growth of carbon nanotubes at column 12, lines 13-6 and 17-22.

In regards to claim 46, Rueckes teaches a method according to claim 42 further comprising the step of stripping the mask from the substrate by chemical dissolution solvent subsequent to the step of depositing the material through the intersticies contained in the mask so as to leave the material deposited on the substrate where the interstitial sites previously existed at column 12, lines 31-42.

In regards to claim 47, Rueckes teaches a method according to claim solvent is THF at column 12, lines 31-42.

In regards to claim 48, Rueckes teaches a method according claim 42 wherein the material precludes carbon nanotube growth at column 11, lines 42-45.

In regards to claim 49, Rueckes teaches a method according claim 42 wherein thestep of depositing the material through the intersticies contained in the periodic arrangement of the mask comprises depositing a portion of the material above a top surface the objects, and further comprising the step of

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dissolving the objects so as to create a freestanding film of material containing perforations corresponding to wherein the interstitial sites previously existed at column 13, lines 16-23.

In regards to claim 52, Rueckes teaches a method according to claim 42 wherein the pattern on the substrate comprises a multi-dimensional structure at column 11, lines 47-53.

In regards to claim 53, Rueckes teaches a method according to claim 42 wherein the material deposited on the substrate comprises features having a vertical height less than about 300 nanometers on an edge thereof, and further wherein the material comprises a catalytic material for growth of carbon nanotubes suited to form a single nanotube at column 12, lines 13-16.

Therefore, it would have been obvious to one having ordinary skill at the time the invention was made to have modified Winningham to include a method for creating a deposition having nanoscale pattern on a substrate, the method comprising: periodic arrangement of objects on a top surface of a supporting liquid at a first given height above suspending a top surface of a substrate; adjusting at least one from a group consisting of top surface of the fluid and the top surface of the substrate position the top surface of the supporting liquid below the top surface of the substrate so as deposit the periodic arrangement objects onto the top surface of the substrate from the suspension on the top surface of the fluid, whereby to create mask; and depositing a material through interstices contained in the mask so as create a pattern on the substrate, since such a

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modification would result in conductive nanotubes and articles that may operate well in contexts having high current densities or in extreme thermal conditions, as described in column 1, lines 50-57 of Rueckes et al.

#### **Conclusion**

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. US Patent No. 6,764,874 to Zhang et al. discloses method of depositing nanotubes.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Renee R Berry whose telephone number is (571) 272-1774. The examiner can normally be reached on M-F 9-5:30.

The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-

free).

Pavid Nelms
Supervisory Patent Examiner

**RRB** 

Technology Center 2800

June 27, 2004